

L Number	Hits	Search Text	DB	Time stamp
1	2416	((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) same (wet near3 (treat\$6 clean\$3))	USPAT; US-PGPUB	2003/03/11 18:56
2	1265	((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) with (wet near3 (treat\$6 clean\$3))	USPAT; US-PGPUB	2003/03/11 18:56
3	1265	((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) near100 (wet near3 (treat\$6 clean\$3))	USPAT; US-PGPUB	2003/03/11 18:56
4	2416	((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) same (wet near3 (treat\$6 clean\$3))) (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) with (wet near3 (treat\$6 clean\$3))) (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) near100 (wet near3 (treat\$6 clean\$3)))	USPAT; US-PGPUB	2003/03/11 18:48
5	877	((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) same (wet near3 (treat\$6 clean\$3))) (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) with (wet near3 (treat\$6 clean\$3))) (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) near100 (wet near3 (treat\$6 clean\$3)))	USPAT; US-PGPUB	2003/03/11 18:39
6	161	propylene near3 glycol near3 mono?methyl near3 ether	USPAT; US-PGPUB	2003/03/11 18:52
7	4725	ethyl near3 lactate	USPAT; US-PGPUB	2003/03/11 18:52
8	182	methyl near3 methoxy near3 propionate	USPAT; US-PGPUB	2003/03/11 18:53
10	1653	2?heptanone	USPAT; US-PGPUB	2003/03/11 18:53
11	1206	ethyl near3 pyruvate	USPAT; US-PGPUB	2003/03/11 18:53
12	146	diethylene near3 glycol near3 mono?methyl near3 ether	USPAT; US-PGPUB	2003/03/11 18:43
13	2333	methyl near3 cellosolve near3 acetate	USPAT; US-PGPUB	2003/03/11 18:54
15	135	ethyl near3 methoxy near3 propionate	USPAT; US-PGPUB	2003/03/11 18:54
16	2471	propylene near3 glycol near3 mono?ethyl near3 ether near3 acetate	USPAT; US-PGPUB	2003/03/11 18:54
17	135	ethyl near3 methoxy near3 propionate	USPAT; US-PGPUB	2003/03/11 18:54
18	2106	methyl near3 lactate	USPAT; US-PGPUB	2003/03/11 18:55
19	973	methyl near3 pyruvate	USPAT; US-PGPUB	2003/03/11 18:55
20	10455	(propylene near3 glycol near3 mono?methyl near3 ether) (ethyl near3 lactate) (methyl near3 methoxy near3 propionate) 2?heptanone (ethyl near3 pyruvate) (diethylene near3 glycol near3 mono?methyl near3 ether) (methyl near3 cellosolve near3 acetate) (ethyl near3 methoxy near3 propionate) (propylene near3 glycol near3 mono?ethyl near3 ether near3 acetate) (ethyl near3 methoxy near3 propionate) (methyl near3 lactate) (methyl near3 pyruvate)	USPAT; US-PGPUB	2003/03/11 18:49

21	17	(((((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) same (wet near3 (treat\$6 clean\$3))) (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) with (wet near3 (treat\$6 clean\$3))) (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) near100 (wet near3 (treat\$6 clean\$3)))) and ((propylene near3 glycol near3 mono?methyl near3 ether) (ethyl near3 lactate) (methyl near3 methoxy near3 propionate) 2?heptanone (ethyl near3 pyruvate) (diethylene near3 glycol near3 mono?methyl near3 ether) (methyl near3 cellosolve near3 acetate) (ethyl near3 methoxy near3 propionate) (propylene near3 glycol near3 mono?ethyl near3 ether near3 acetate) (ethyl near3 methoxy near3 propionate) (methyl near3 lactate) (methyl near3 pyruvate))	USPAT; US-PGPUB	2003/03/11 18:49
22	46	propylene near3 glycol near3 mono?methyl near3 ether	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:52
23	440	ethyl near3 lactate	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:52
24	28	methyl near3 methoxy near3 propionate	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:53
25	90	2?heptanone	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:53
26	72	ethyl near3 pyruvate	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:53
27	213	methyl near3 cellosolve near3 acetate	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:54
28	13	ethyl near3 methoxy near3 propionate	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:54
29	140	propylene near3 glycol near3 mono?ethyl near3 ether near3 acetate	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:54
30	13	ethyl near3 methoxy near3 propionate	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:54
31	227	methyl near3 lactate	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:55
32	63	methyl near3 pyruvate	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:55
33	1121	((propylene near3 glycol near3 mono?methyl near3 ether) (ethyl near3 lactate) (methyl near3 methoxy near3 propionate) 2?heptanone (ethyl near3 pyruvate) (methyl near3 cellosolve near3 acetate) (ethyl near3 methoxy near3 propionate) (propylene near3 glycol near3 mono?ethyl near3 ether near3 acetate) (ethyl near3 methoxy near3 propionate) (methyl near3 lactate) (methyl near3 pyruvate)	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:56
34	669	(((((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) same (wet near3 (treat\$6 clean\$3))	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:56
35	461	(((((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) with (wet near3 (treat\$6 clean\$3))	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:56

36	460	((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) near100 (wet near3 (treat\$6 clean\$3))	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:57
37	669	((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) same (wet near3 (treat\$6 clean\$3))) (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) with (wet near3 (treat\$6 clean\$3))) (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) near100 (wet near3 (treat\$6 clean\$3)))	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:57
38	0	((propylene near3 glycol near3 mono?methyl near3 ether) (ethyl near3 lactate) (methyl near3 methoxy near3 propionate) 2?heptanone (ethyl near3 pyruvate) (methyl near3 cellosolve near3 acetate) (ethyl near3 methoxy near3 propionate) (propylene near3 glycol near3 mono?ethyl near3 ether near3 acetate) (ethyl near3 methoxy near3 propionate) (methyl near3 lactate) (methyl near3 pyruvate)) and (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) same (wet near3 (treat\$6 clean\$3))) (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) with (wet near3 (treat\$6 clean\$3))) (((silicon near3 nitride) S3N4 ("Si.sub.3" adj "N.sub.4")) or (silicon nitride oxide)) near100 (wet near3 (treat\$6 clean\$3)))	EPO; JPO; DERWENT; IBM_TDB	2003/03/11 18:57
-	117346	((uncoated\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 oxynitride) oxynitride SiON))	USPAT; US-PGPUB	2003/03/03 12:21
-	40762	((uncoated\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 oxynitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)	USPAT; US-PGPUB	2003/03/03 12:22
-	292	((uncoated\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 oxynitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (far near3 infrared (far near3 IR))	USPAT; US-PGPUB	2003/03/03 12:23
-	103	((uncoated\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 oxynitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (far near3 infrared (far near3 IR))) and (organic near5 (film material layer))	USPAT; US-PGPUB	2003/03/03 12:24
-	117346	((uncoated\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 oxynitride) oxynitride SiON))	USPAT; US-PGPUB	2003/03/03 15:45
-	40762	((uncoated\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 oxynitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)	USPAT; US-PGPUB	2003/03/03 15:46
-	292	((uncoated\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 oxynitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (far near3 infrared (far near3 IR))	USPAT; US-PGPUB	2003/03/03 15:47

-	103	(((((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 oxynitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (far near3 infrared (far near3 IR))) and (organic near5 (film material layer)))	USPAT; US-PGPUB	2003/03/03 15:47
-	103	(((((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 oxynitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (far near3 infrared (far near3 IR))) and (organic near5 (film material layer)))	USPAT; US-PGPUB	2003/03/03 15:43
-	117361	((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride) oxynitride SiON)))	USPAT; US-PGPUB	2003/03/03 17:47
-	117413	((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride) oxynitride oxinitride SiON)))	USPAT; US-PGPUB	2003/03/03 15:46
-	40789	((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride) oxynitride oxinitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)	USPAT; US-PGPUB	2003/03/03 17:47
-	292	(((((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride) oxynitride oxinitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (far near3 infrared (far near3 IR)))	USPAT; US-PGPUB	2003/03/03 17:48
-	103	(((((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride) oxynitride oxinitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (far near3 infrared (far near3 IR))) and (organic near5 (film material layer)))	USPAT; US-PGPUB	2003/03/03 17:48
-	58420	((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride) oxynitride SiON)))	EPO; JPO; DERWENT; IBM_TDB	2003/03/03 17:47
-	4065	((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)	EPO; JPO; DERWENT; IBM_TDB	2003/03/03 17:48
-	2	(((((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (far near3 infrared (far near3 IR)))	EPO; JPO; DERWENT; IBM_TDB	2003/03/03 17:48
-	95	(((((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (organic near5 (film material layer)))	EPO; JPO; DERWENT; IBM_TDB	2003/03/03 17:52
-	0	(((((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (organic near5 (film material layer))) and infrared	EPO; JPO; DERWENT; IBM_TDB	2003/03/03 17:52

-	6	((((unercoat\$3) ((silicon near3 nitride) SiN Si3N4 ("Si.sub.3" adj "N.sub.4")) ((silicon near3 (oxynitride oxinitride)) oxynitride SiON))) and ((wet near3 clean\$3) clean\$3 treat\$3)) and (organic near5 (film material layer))) and irradiat\$3	EPO; JPO; DERWENT; IBM_TDB	2003/03/03 17:52
---	---	--	----------------------------------	------------------